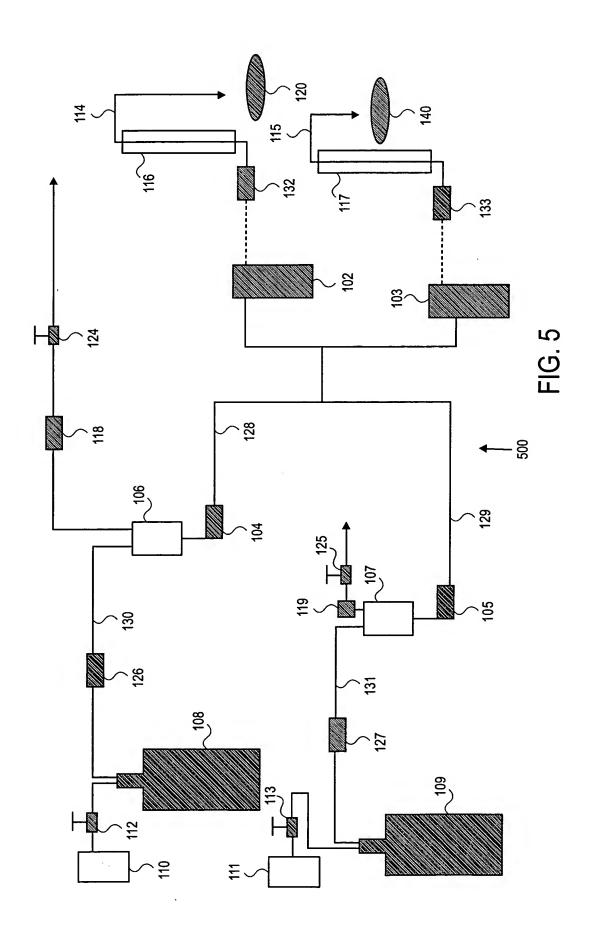
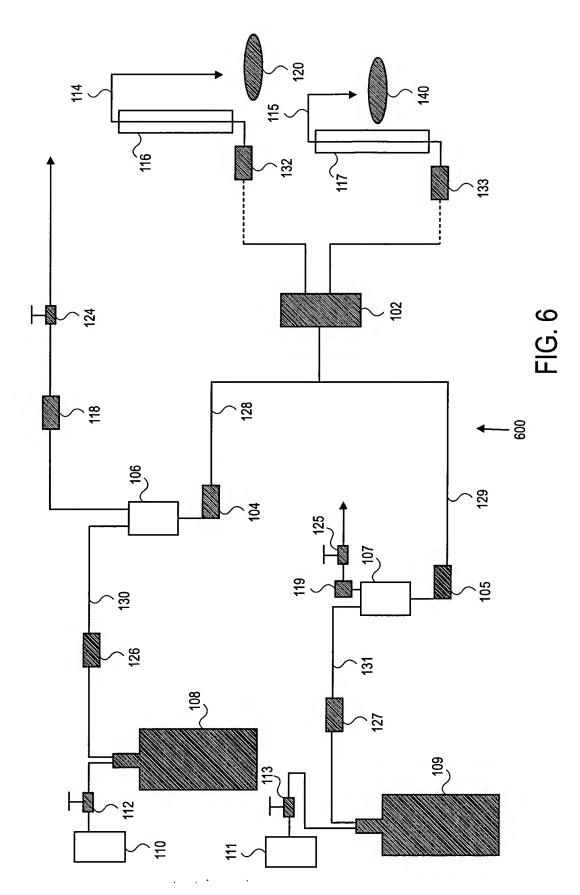


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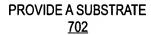
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DISPENSE POLYMER SOLUTION (E.G., PHOTORESIST POLYMER SOLUTION) ONTO A SUBSTRATE SURFACE USING A COATING SYSTEM HAVING A PUMP CONNECTED IN-LINE WITH A BUFFER TANK AND A POLYMER SOLUTION SOURCE SUCH THAT THERE IS A CONTINUOUS FLUID PATH FROM THE POLYMER SOLUTION SOURCE THROUGH THE BUFFER TANK AND TO THE PUMP

<u>704</u>



FIG. 7

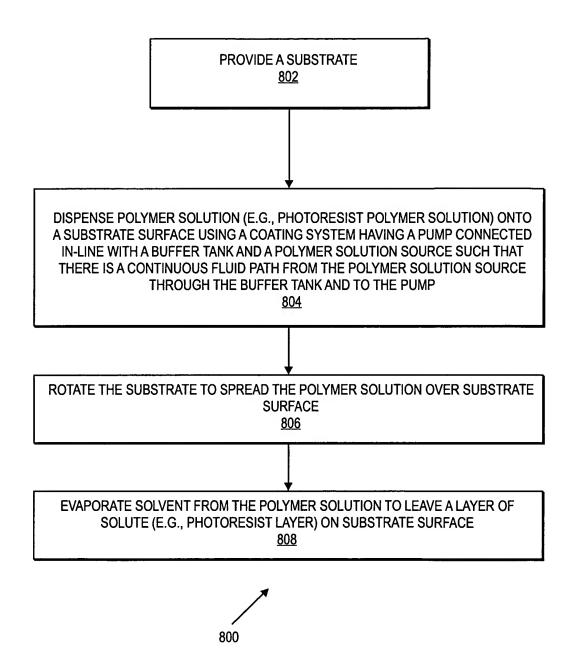


FIG. 8

DISPENSE POLYMER SOLUTION (E.G., PHOTORESIST POLYMER SOLUTION) ONTO A SUBSTRATE SURFACE USING A COATING SYSTEM HAVING A PUMP CONNECTED IN-LINE WITH A BUFFER TANK AND A POLYMER SOLUTION SOURCE SUCH THAT THERE IS A CONTINUOUS FLUID PATH FROM THE POLYMER SOLUTION SOURCE THROUGH THE BUFFER TANK AND TO THE PUMP 904

APPLYING PRESSURE BY PRESSING DOWN ON A MOMENTARY VALVE (FOR A FEW SECONDS) TO TRANSFER POLYMER SOLUTION FROM THE POLYMER SOLUTION SOURCE INTO THE BUFFER TANK 906



FIG. 9